

(19)
(12)

(KR)
(A)

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2004 10 22

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10-2003-0024106

(22)

2003 04 16

(71)

20

(72)

299-24

(74)

:

(54)

E L

EL ,

, (tension) 가
(align) (simulation)

, .

6

EL,

1a 1d EL

2a 2d EL

3a EL

가

1b
2a (bridge)
2a 2d EL
가 2a 1 (11) (10) 1 (11) (bus electrode) 1 (11)
() 2 (12)
(10) (13) (14)
() 가 (14) (10) (align) 2b
, R
, 2c 2d G B
()
(10) 3b 3a (10) (15)가 (array)
(16)
3b (8)
, (8) 가 (tension) 가 가 (Shadow)
, 가 가 (shift) (simulation)

EL 1 2 EL
EL , EL

, EL R, G, B .
 , 가 R, G, B .
 , .
 , .
 4 , 5 , 6 .
 (20) 6 , (20-1) (20-2) .
 가 (20-1) 4 , (tension) 가 .
 , (20-2) 5 (20-1) .
 (Open)
 , (20-2) (holder)(30) .
 , (20-1) (20-2) (20) (20-2) .
 (20-1)
 (20) EL .
 7 EL , (40) ITO 1 .
 1 2 .
 (40) (40-1) .
 8 EL , .
 (blank mask)
 , (20) (40) (Align) (20) .
 R, G, B .
 , Mg - Ag , Al (encapsulation)
 EL .
 EL 가 .
 (tension) 가 .
 , (simulation) .
 , .

가

(57)

1.

2.

1

3.

1

2

EL

EL

EL

4.

3

EL

R, G, B

EL

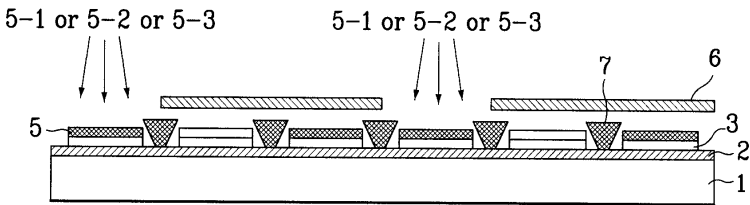
5.

1

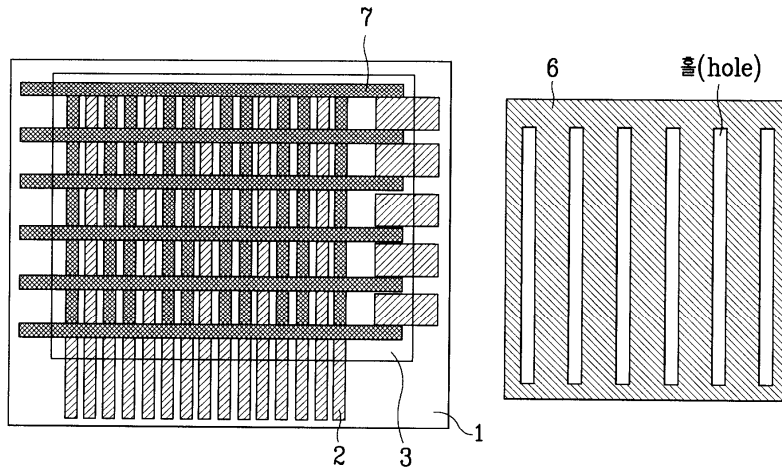
가 R, G, B

EL

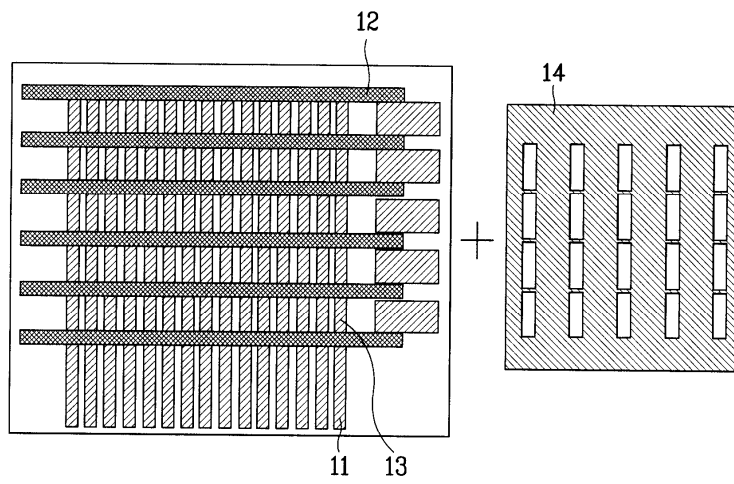
1a



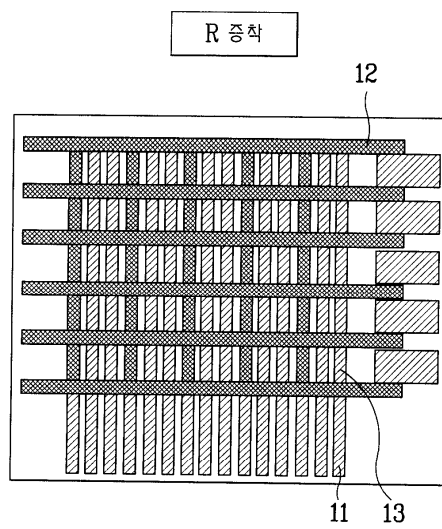
1b



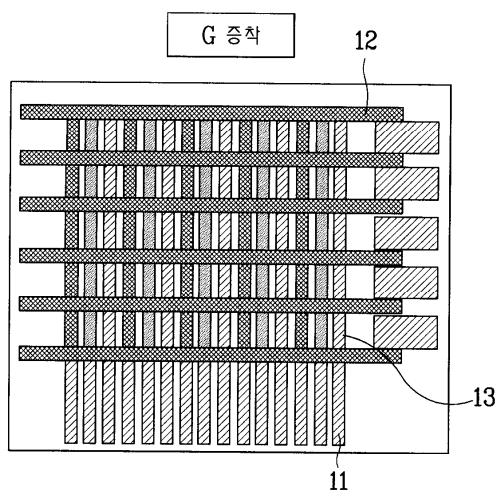
2a



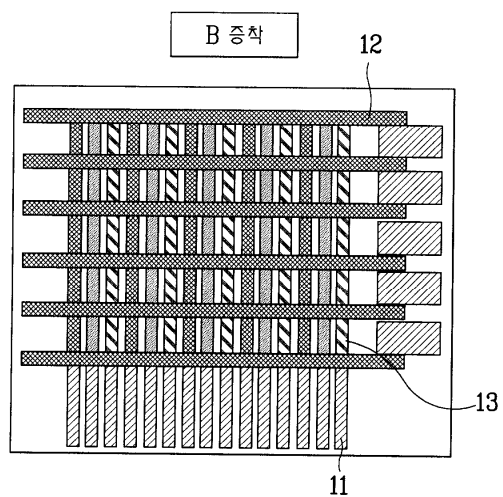
2b



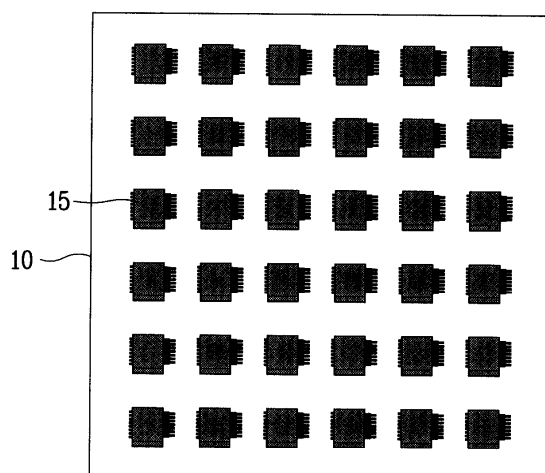
2c



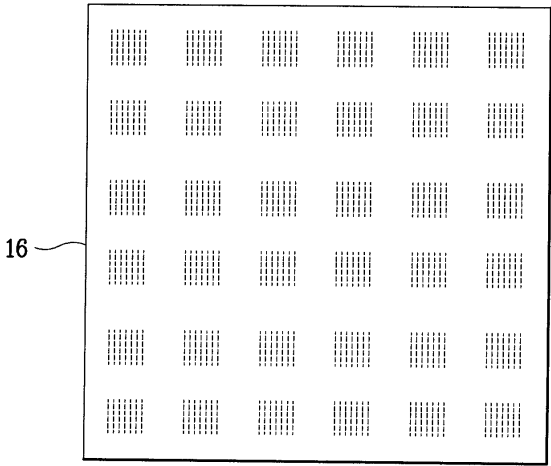
2d



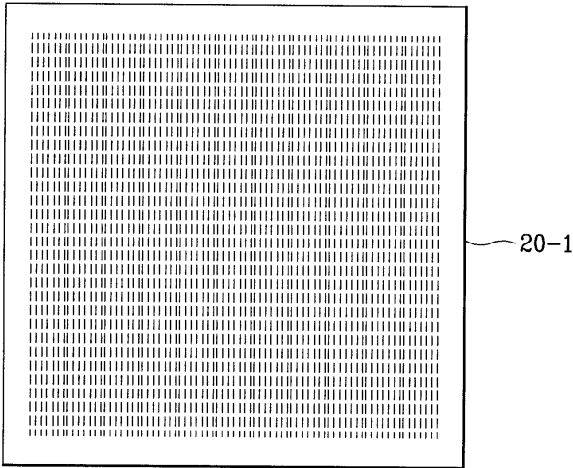
3a



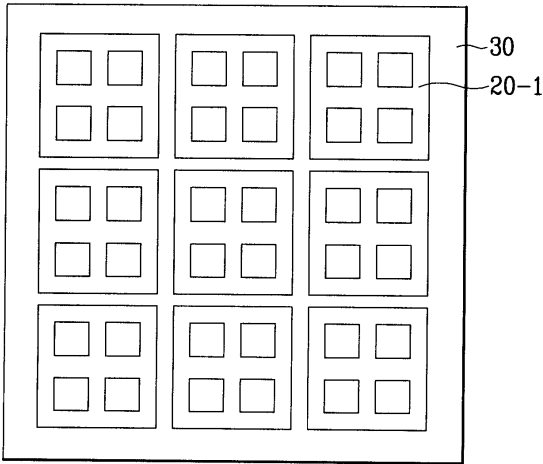
3b



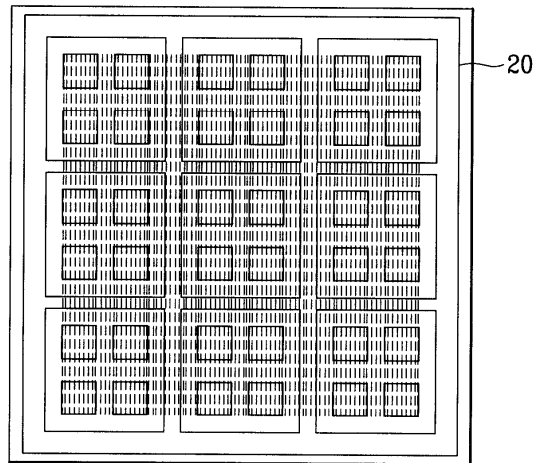
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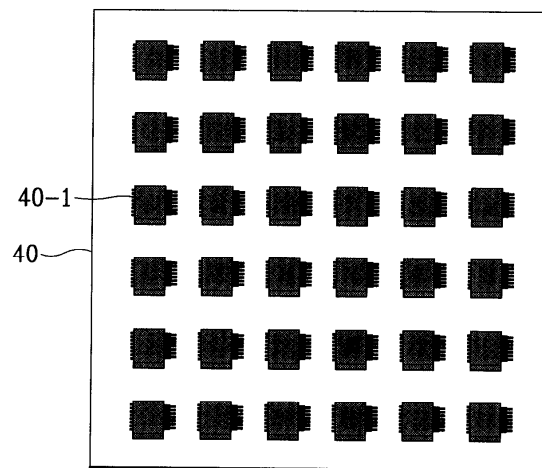
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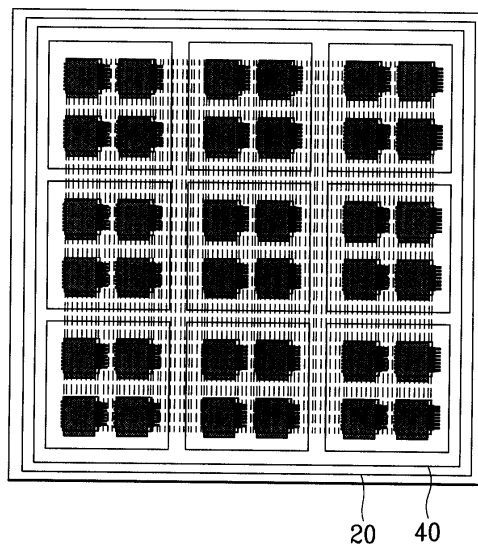
6



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专利名称(译)	阴影掩模和使用其的有机EL显示装置的制造方法		
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代理人(译)	金勇 新昌		
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外部链接	Espacenet		

摘要(译)

本发明涉及提供荫罩的制造方法和使用该方法的有机电致发光显示装置。并且包括具有阴影掩模阻挡发光区域的结构 of 的次级阴影掩模，其形成的孔图案阴影掩模使得孔均匀地分布在非发射区域中的每个人和非发射区域的孔图案面具。因此，通过使用掩模，对于掩模孔移位的模拟是容易的，因为当向掩模添加张力时，自由掩模可以作为整个掩模接收功率，以便保护均匀的掩模凹陷并且便于对准。此外，由于在所需位置上形成发光层，因此可以防止色移现象。有机EL和荫罩。

